

Abstract

Ethylenediaminetetraacetic Acid or its Ammonium Salt Semiconductor

Process Residue Removal Composition and Process

5 An ethylenediaminetetraacetic acid or a mono- di- tri- or tetraammonium salt 5
thereof residue cleaning composition removes photoresist and other residue
from integrated circuit substrates. The balance of the composition is desirably
made up of water, preferably high purity deionized water, or another suitable
polar solvent. A process for removing photoresist or other residue from a
10 substrate, such as an integrated circuit semiconductor wafer including titanium
metallurgy, comprises contacting the substrate with the composition for a time
and at a temperature sufficient to remove the photoresist or other residue from
the substrate. Use of the ethylenediaminetetraacetic acid or a mono- di- tri- or
tetraammonium salt thereof in the composition and process provides superior
15 residue removal without attacking titanium or other metallurgy, oxide or nitride
layers on the substrate.

No Figure